

10/760,497, 7/25/05, 89A; CA-structure search

L17 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2004:246983 CAPLUS
 DN 140:294802
 TI Image forming material
 IN Iwato, Kaoru; Sorori, Tadahiro
 PA Fuji Photo Film Co., Ltd., Japan
 SO Eur. Pat. Appl., 94 pp.
 CODEN: EPXXDW
 DT Patent
 LA English
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1400350	A2	20040324	EP 2003-20551	20030917
	EP 1400350	A3	20040414		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004109320	A2	20040408	JP 2002-269900	20020917
	JP 2004126049	A2	20040422	JP 2002-287818	20020930
	US 2004067435	A1	20040408	US 2003-662534	20030916
PRAI	JP 2002-269900	A	20020917		
	JP 2002-287818	A	20020930		

OS MARPAT 140:294802

AB Image-forming materials (e.g., planog. **printing plate** precursors) comprising a support and an image forming layer which is laminated on the support are described in which the image-forming layer contains at least a water-insol. and alkali-soluble polymer compound and a compound (especially an onium salt) having a structure represented by the general

formula X-M⁺ (X⁻ = an anion containing ≥1 substituent having an alkali-dissociating proton; and M⁺ = a counter cation which is an atomic group having an absorption maximum at a wavelength in the 760-1200 nm range) and having an absorption maximum at a wavelength in the range 760-1200 nm. The materials may addnl. include a light-heat converting agent.

IT 137309-11-6 675190-76-8 675190-85-9

RL: TEM (Technical or engineered material use); USES (Uses)
 (image forming materials containing salts and polymers)

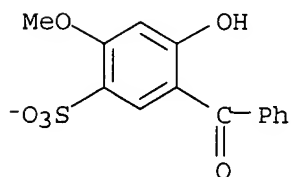
RN 137309-11-6 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7

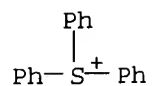
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

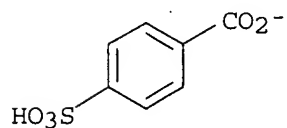
CMF C18 H15 S



RN 675190-76-8 CAPLUS
 CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

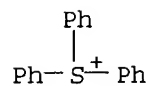
CM 1

CRN 96296-44-5
 CMF C7 H5 O5 S



CM 2

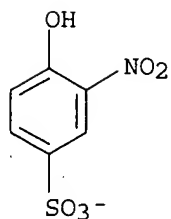
CRN 18393-55-0
 CMF C18 H15 S



RN 675190-85-9 CAPLUS
 CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

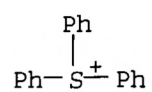
CM 1

CRN 154936-89-7
 CMF C6 H4 N O6 S



CM 2

CRN 18393-55-0
 CMF C18 H15 S



=>

L19 ANSWER 1 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2005:467854 CAPLUS

DN 143:16503

TI **Photosensitive** composition containing specific sulfonic acid-generating compound for use in the **photosensitive** composition, and pattern forming method using the **photosensitive** composition

IN Wada, Kenji; Kodama, Kunihiro

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 133 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1536285	A2	20050601	EP 2004-27406	20041118
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR, IS, YU				
	JP 2005173549	A2	20050630	JP 2004-222931	20040730
	US 2005123859	A1	20050609	US 2004-993094	20041122
PRAI	JP 2003-392790	A	20031121		
	JP 2004-222931	A	20040730		

TI **Photosensitive** composition containing specific sulfonic acid-generating compound for use in the **photosensitive** composition, and pattern forming method using the **photosensitive** composition

AB Disclosed is a **photosensitive** composition comprising a compound capable of generating a specific sulfonic acid upon irradiation with actinic rays or a radiation; a . . . a specific sulfonic acid upon irradiation with an actinic ray or a radiation; and a pattern forming method using a **photosensitive** composition comprising a compound capable of generating a specific sulfonic acid upon irradiation with an actinic ray or a radiation..

ST **photosensitive** compn sulfonate acid generating pattern
photoresist

IT Photolithography
Photoresists

(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT Acids, preparation

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(precursors; **photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT 852572-36-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(delphotosensitive composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT 112-53-8, 1-Dodecanol 313-50-8D, Perfluorobenzenesulfonic acid, methylpropanyl ester 3744-08-9, Triphenylsulfonium iodide 852572-07-7
RL: RCT (Reactant); RACT (Reactant or reagent)

(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT 852572-09-9P 852572-11-3P 852572-13-5P 852572-15-7P 852572-17-9P
852572-19-1P 852572-21-5P 852572-23-7P 852572-25-9P

852572-27-1P 852572-29-3P 852572-31-7P 852572-33-9P 852572-34-0P
 852572-35-1P 852572-37-3P 852572-38-4P 852572-39-5P 852572-41-9P
 852572-42-0P 852572-44-2P 852572-46-4P 852572-47-5P 852572-48-6P
 852572-49-7P 852572-52-2P 852572-54-4P 852572-56-6P 852572-58-8P
 852572-60-2P 852572-62-4P 852572-64-6P 852572-66-8P 852572-68-0P
 852572-69-1P 852572-70-4P 852572-71-5P 852572-72-6P 852572-73-7P
 852572-74-8P 852572-76-0P 852572-77-1P 852572-78-2P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

IT 852572-19-1P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(**photosensitive** composition containing specific sulfonic acid-generating compound for use in **photosensitive** composition, and pattern forming method using the **photosensitive** composition)

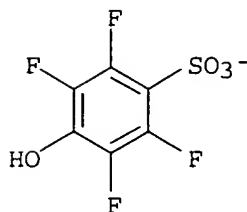
RN 852572-19-1 CAPLUS

CN Sulfonium, triphenyl-, salt with 2,3,5,6-tetrafluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 852572-18-0

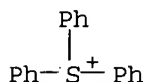
CMF C6 H F4 O4 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 2 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2005:256554 CAPLUS

DN 142:345143

TI Negative-working photopolymerizable photoimaging composition containing specific polymerization initiator for **image** recording materials

IN Shimada, Kazuto

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 92 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

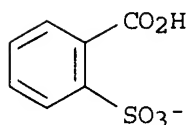
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2005077984	A2	20050324	JP 2003-311254	20030903
PRAI	JP 2003-311254		20030903		
TI	Negative-working photopolymerizable photoimaging composition containing specific polymerization initiator for image recording materials				
ST	neg photopolymerizable photoimaging compn image recording radical polymn initiator				
IT	Photoimaging materials (photopolymerizable; neg.-working photopolymerizable photoimaging composition for image recording materials)				
IT	Polymerization catalysts (radical; neg.-working photopolymerizable photoimaging composition for image recording materials)				
IT	709037-32-1 790622-95-6 848421-84-1 848421-85-2 848421-86-3				
	848421-87-4 848421-89-6 848421-90-9 848421-91-0				
	848421-92-1 848440-63-1				
	RL: CAT (Catalyst use); USES (Uses) (radical polymerization initiator)				
IT	848421-86-3 848421-87-4 848421-89-6 848440-63-1				
	RL: CAT (Catalyst use); USES (Uses) (radical polymerization initiator)				
RN	848421-86-3 CAPLUS				
CN	Sulfonium, triphenyl-, salt with 2-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)				

CM 1

CRN 58592-21-5

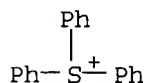
CMF C7 H5 O5 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



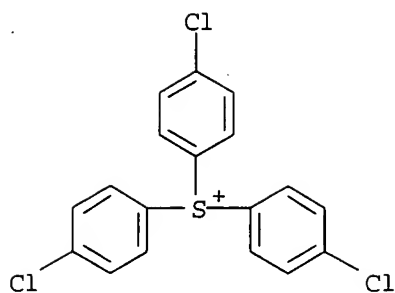
RN 848421-87-4 CAPLUS

CN Sulfonium, tris(4-chlorophenyl)-, salt with 4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 125853-07-8

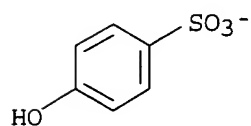
CMF C18 H12 Cl3 S



CM 2

CRN 45935-73-7

CMF C6 H5 O4 S



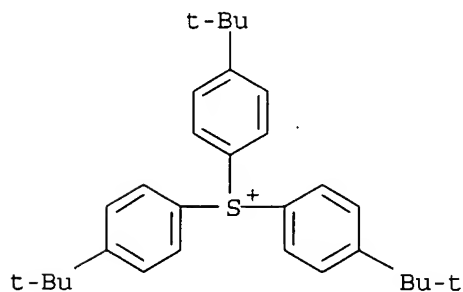
RN 848421-89-6 CAPLUS

CN Sulfonium, tris[4-(1,1-dimethylethyl)phenyl]-, salt with 2-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 91815-56-4

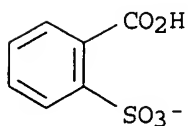
CMF C30 H39 S



CM 2

CRN 58592-21-5

CMF C7 H5 O5 S



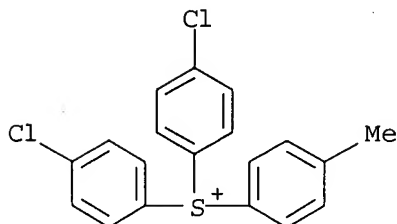
RN 848440-63-1 CAPLUS

CN Sulfonium, bis(4-chlorophenyl)(4-methylphenyl)-, salt with 5-sulfo-1,3-benzenedicarboxylic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 667888-57-5

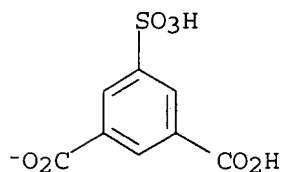
CMF C19 H15 Cl2 S



CM 2

CRN 65086-74-0

CMF C8 H5 O7 S



L19 ANSWER 3 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:963502 CAPLUS

DN 141:417925

TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same

IN Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 99 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004318046	A2	20041111	JP 2003-293188	20030813
PRAI	JP 2003-94329	A	20030331		

TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same

AB Disclosed is the pos.-working vacuum-UV **photoresist** composition especially suited for a F2 excimer laser (157 nm) comprising (a) a resin having a repeating unit FR0C-CFR1, FR0C-CF(OR2), . . .

ST pos working vacuum UV **photoresist** compn patterning photolithog

IT Photolithography

Photoresists

(pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 66003-78-9 144317-44-2 **756532-52-2**

RL: TEM (Technical or engineered material use); USES (Uses)

(photoacid; pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 791849-04-2P
 RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 791848-97-0 791848-99-2 791849-01-9 791849-07-5 791849-10-0
 791849-12-2 791849-14-4 791849-15-5 791849-17-7 791853-95-7
 791853-96-8 791853-98-0 791854-01-8 791854-03-0
 RL: PRP (Properties); TEM (Technical or engineered material use); USES (Uses)
 (pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

IT 699-95-6
 RL: RCT (Reactant); RACT (Reactant or reagent)
 (preparation of resin for pos.-working vacuum-UV **photoresist** composition)

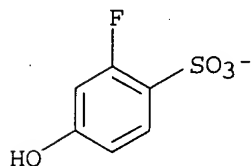
IT 142507-56-0P 791849-03-1P 791849-18-8P 791849-19-9P
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
 (preparation of resin for pos.-working vacuum-UV **photoresist** composition)

IT **756532-52-2**
 RL: TEM (Technical or engineered material use); USES (Uses)
 (photoacid; pos.-working vacuum-UV **photoresist** composition containing fluoropolymer and photoacid)

RN 756532-52-2 CAPLUS
 CN Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

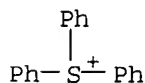
CM 1

CRN 756532-51-1
 CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0
 CMF C18 H15 S



L19 ANSWER 4 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2004:960408 CAPLUS
 DN 141:417914
 TI Positive-working vacuum-UV **photoresist** composition and patterning method using the same
 IN Sasaki, Tomoya
 PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 113 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

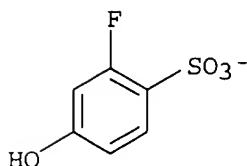
FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004318045	A2	20041111	JP 2003-293175	20030813
PRAI	JP 2003-96391	A	20030331		
TI	Positive-working vacuum-UV photoresist composition and patterning method using the same				
AB	Disclosed is the pos.-working vacuum-UV photoresist composition comprising (a) a resin having a repeating unit $-C(OY)\{-CR_{50}R_{51}R_{52}\}\{-CR_{53}R_{54}R_{55}\}$ ($R_{50-55} = H, F, \text{alkyl}$; and $Y = H, \text{organic}$).				
ST	pos working resist photoresist compn patterning photolithog; vacuum UV photoresist				
IT	Photolithography (pos.-working vacuum-UV photoresist composition containing resins and photoacid)				
IT	Photoresists (vacuum-UV; pos.-working vacuum-UV photoresist composition containing resins and photoacid)				
IT	66003-78-9 144317-44-2 756532-52-2 RL: TEM (Technical or engineered material use); USES (Uses) (photoacid; pos.-working vacuum-UV photoresist composition from)				
IT	262617-10-7P, tert-Butyl acrylate-norbornene-tetrafluoroethylene copolymer 792284-28-7P RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (pos.-working vacuum-UV photoresist composition from)				
IT	105935-25-9	357397-06-9	365568-64-5	622378-55-6	680603-11-6
	792285-90-6	792286-10-3	792286-34-1	792286-57-8	792286-72-7
	792286-88-5	792287-05-9	792287-44-6	792916-51-9	792916-53-1
	792916-55-3				
	RL: TEM (Technical or engineered material use); USES (Uses) (pos.-working vacuum-UV photoresist composition from)				
IT	756532-52-2 RL: TEM (Technical or engineered material use); USES (Uses) (photoacid; pos.-working vacuum-UV photoresist composition from)				
RN	756532-52-2 CAPLUS				
CN	Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)				

CM 1

CRN 756532-51-1

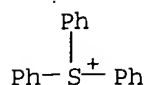
CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 5 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:753223 CAPLUS

DN 141:268557

TI Positive resist composition and method of forming a resist pattern using the same

IN Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 80 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1457819	A2	20040915	EP 2004-4961	20040303
	EP 1457819	A3	20050622		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
	JP 2004279471	A2	20041007	JP 2003-67010	20030312
PRAI	JP 2003-67010	A	20030312		

AB A pos. **photoresist** composition comprises (A) a resin comprising specific repeating units and coming to have enhanced solubility in an alkaline developing solution.

ST pos **photoresist** compn pattern

IT Positive photoresists

(pos. **photoresist** composition for forming resist pattern)

IT 66003-78-9 144317-44-2 205682-99-1 365971-61-5 365971-70-6

756532-52-2 756532-53-3

RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator; pos. **photoresist** composition for forming resist pattern)

IT 756532-32-8P 756532-34-0P 756532-37-3P 756532-38-4P 756532-39-5P
756532-40-8P 756532-41-9P 756532-42-0P 756532-44-2P 756532-45-3P
756532-47-5P 756532-48-6P 756532-50-0P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos. **photoresist** composition for forming resist pattern)

IT 75-07-0, Acetaldehyde, reactions 107-30-2, Chloromethyl methyl ether 802-93-7, 1,3-Bis(2-hydroxyhexafluoroisopropyl)benzene 1826-67-1, Vinylmagnesium bromide

RL: RCT (Reactant); RACT (Reactant or reagent)

(pos. **photoresist** composition for forming resist pattern)

IT 501935-24-6P 585573-34-8P 585573-35-9P 585573-59-7P

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)

(pos. **photoresist** composition for forming resist pattern)

IT 756532-52-2

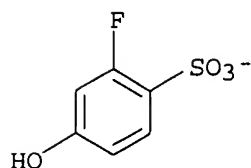
RL: TEM (Technical or engineered material use); USES (Uses)

(acid generator; pos. **photoresist** composition for forming resist pattern)

RN 756532-52-2 CAPLUS

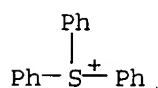
CN Sulfonium, triphenyl-, salt with 2-fluoro-4-hydroxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CRN 756532-51-1
CMF C6 H4 F O4 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 6 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:633141 CAPLUS

DN 141:181996

TI **Image** forming material

IN Iwato, Kaoru

PA Fuji Photo Film Co., Ltd., Japan

SO U.S. Pat. Appl. Publ., 67 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2004152012	A1	20040805	US 2004-760497	20040121
	JP 2004226794	A2	20040812	JP 2003-15905	20030124
	JP 2004233854	A2	20040819	JP 2003-24499	20030131
PRAI	JP 2003-15905	A	20030124		
	JP 2003-24499	A	20030131		

OS MARPAT 141:181996

TI **Image** forming material

AB The present invention relates to an **image** forming material having, on a substrate, an **image** forming layer that includes at least (A) a novolac type phenolic resin containing phenol as a structural unit, (B) a . . .

ST pos planog printing plate **image** material

IT Phenolic resins, uses

RL: TEM (Technical or engineered material use); USES (Uses)
(novolak; pos. planog. printing plate **image** forming material containing)

IT Printing plates

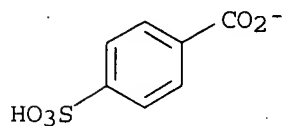
(planog.; pos. planog. printing plate **image** forming material)

IT 445497-24-5 733046-76-9 733046-78-1 733046-80-5 733046-82-7
733046-84-9 733046-85-0 733046-87-2

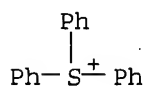
RL: TEM (Technical or engineered material use); USES (Uses)
(ammonium compound; pos. planog. printing plate **image** forming material containing)

IT 121438-28-6 504387-13-7 675190-76-8 675190-77-9
675190-84-8 675190-90-6 675190-91-7 675190-93-9 675190-98-4

675190-99-5 675191-00-1 675191-03-4 675588-03-1 675588-04-2
 RL: TEM (Technical or engineered material use); USES (Uses)
 (onium salt; pos. planog. printing plate **image** forming
 material containing)
 IT 35464-74-5, m-Cresol-p-cresol-formaldehyde-phenol copolymer 56700-20-0,
 Formaldehyde-phenol-2,5-xyleneol copolymer
 RL: PRP (Properties); TEM (Technical or engineered material use); USES
 (Uses)
 (pos. planog. printing plate **image** forming material containing)
 IT **675190-76-8**
 RL: TEM (Technical or engineered material use); USES (Uses)
 (onium salt; pos. planog. printing plate **image** forming
 material containing)
 RN 675190-76-8 CAPLUS
 CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA
 INDEX NAME)
 CM 1
 CRN 96296-44-5
 CMF C7 H5 O5 S



CM 2
 CRN 18393-55-0
 CMF C18 H15 S



L19 ANSWER 7 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 2004:246983 CAPLUS
 DN 140:294802
 TI **Image** forming material
 IN Iwato, Kaoru; Sorori, Tadahiro
 PA Fuji Photo Film Co., Ltd., Japan
 SO Eur. Pat. Appl., 94 pp.
 CODEN: EPXXDW
 DT Patent
 LA English
 FAN.CNT 1

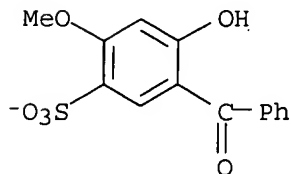
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1400350	A2	20040324	EP 2003-20551	20030917
	EP 1400350	A3	20040414		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004109320	A2	20040408	JP 2002-269900	20020917
	JP 2004126049	A2	20040422	JP 2002-287818	20020930
	US 2004067435	A1	20040408	US 2003-662534	20030916

PRAI JP 2002-269900 A 20020917
 JP 2002-287818 A 20020930
 OS MARPAT 140:294802
 TI **Image** forming material
 AB **Image**-forming materials (e.g., planog. printing plate precursors) comprising a support and an **image** forming layer which is laminated on the support are described in which the **image**-forming layer contains at least a water-insol. and alkali-soluble polymer compound and a compound (especially an onium salt) having a structure. . . . range)
 and having an absorption maximum at a wavelength in the range 760-1200 nm. The materials may addnl. include a light-**heat** converting agent.
 ST planog printing plate precursor salt polymer; onium salt polymer **image** forming material
 IT Fluoropolymers, uses
 RL: TEM (Technical or engineered material use); USES (Uses)
 (**image** forming materials containing salts and polymers)
 IT Phenolic resins, uses
 RL: TEM (Technical or engineered material use); USES (Uses)
 (novolak; **image** forming materials containing salts and polymers)
 IT Printing plates
 (planog.; **image** forming materials containing salts and polymers)
 IT 56992-87-1P, N-(p-Aminosulfonylphenyl)methacrylamide
 RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT (Reactant or reagent)
 (**image** forming materials containing salts and polymers)
 IT 463312-06-3P, Acrylonitrile-N-(p-Aminosulfonylphenyl)methacrylamide-ethyl methacrylate-methyl methacrylate copolymer
 RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (**image** forming materials containing salts and polymers)
 IT 118590-23-1 121438-28-6 **137309-11-6** 207793-00-8
 216861-97-1 221388-40-5 221388-40-5 501332-52-1 504387-13-7
675190-76-8 675190-77-9 675190-78-0 675190-80-4
 675190-82-6 675190-84-8 **675190-85-9** 675190-87-1
 675190-90-6 675190-91-7 675190-92-8 675190-93-9 675190-95-1
 675190-97-3 675190-98-4 675190-99-5 675191-00-1 675191-01-2
 675191-02-3 675191-03-4 675191-04-5 675191-05-6 675191-06-7
 675191-07-8 675191-08-9 675191-09-0 675191-10-3 675191-11-4
 675191-12-5 675191-14-7 675191-15-8 675191-16-9 675191-17-0
 675191-18-1 675191-19-2 675191-20-5 675588-03-1 675588-04-2
 675588-05-3 675588-06-4 675588-07-5 675588-08-6
 RL: TEM (Technical or engineered material use); USES (Uses)
 (**image** forming materials containing salts and polymers)
 IT **137309-11-6 675190-76-8 675190-85-9**
 RL: TEM (Technical or engineered material use); USES (Uses)
 (**image** forming materials containing salts and polymers)
 RN 137309-11-6 CAPLUS
 CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7

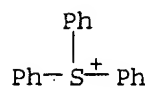
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



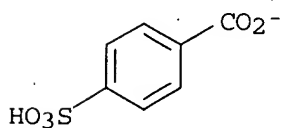
RN 675190-76-8 CAPLUS

CN Sulfonium, triphenyl-, salt with 4-sulfobenzoic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 96296-44-5

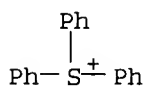
CMF C7 H5 O5 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



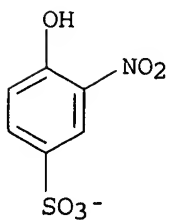
RN 675190-85-9 CAPLUS

CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

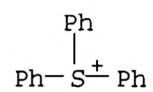
CRN 154936-89-7

CMF C6 H4 N O6 S



CM 2

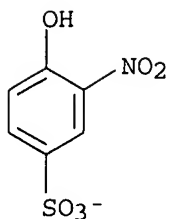
CRN 18393-55-0
CMF C18 H15 S



RN 675190-85-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 4-hydroxy-3-nitrobenzenesulfonic acid
(1:1) (9CI) (CA INDEX NAME)

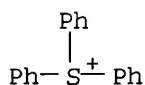
CM 1

CRN 154936-89-7
CMF C6 H4 N O6 S



CM 2

CRN 18393-55-0
CMF C18 H15 S



L19 ANSWER 8 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:750701 CAPLUS

DN 139:283396

TI Sulfonium salts for photoacid generators, their manufacture,
photosensitive resin compositions containing them, and their argon
laser-sensitive photoresists

IN Tarumoto, Naohiro; Yamaoka, Tsugio; Yoshikawa, Katsumasa; Yamazaki, Hajime

PA Hodogaya Chemical Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003267968	A2	20030925	JP 2002-68269	20020313
PRAI	JP 2002-68269		20020313		

OS MARPAT 139:283396

TI Sulfonium salts for photoacid generators, their manufacture,
photosensitive resin compositions containing them, and their argon
laser-sensitive photoresists

ST sulfonium photoacid generator **photoresist** argon laser

IT 605655-38-7

RL: CAT (Catalyst use); USES (Uses)

(photoacid generators; sulfonium salt photoacid generators for Ar
laser-sensitive photoresists)

IT 605655-38-7

RL: CAT (Catalyst use); USES (Uses)

(photoacid generators; sulfonium salt photoacid generators for Ar

laser-sensitive photoresists)

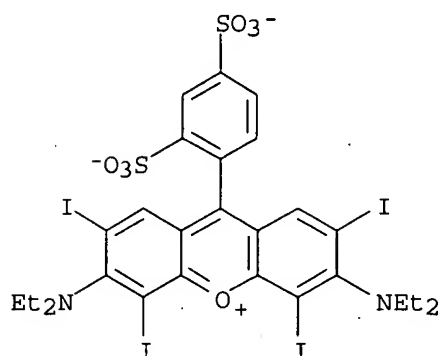
RN 605655-38-7 CAPLUS

CN Xanthylum, 3,6-bis(diethylamino)-9-(2,4-disulfophenyl)-2,4,5,7-tetraiodo-, inner salt, ion(1-), triphenylsulfonium (9CI) (CA INDEX NAME)

CM 1

CRN 605655-37-6

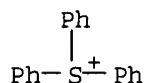
CMF C27 H25 I4 N2 O7 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 9 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:750689 CAPLUS

DN 139:267987

TI Pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light, their preparation, and their positive **photosensitive** resin compositions and **photosensitive** materials

IN Tarumoto, Naohiro; Yamaoka, Tsugio; Yoshikawa, Katsumasa; Yamazaki, Hajime

PA Hodogaya Chemical Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003267949	A2	20030925	JP 2002-67267	20020312
PRAI	JP 2002-67267		20020312		

OS MARPAT 139:267987

TI Pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light, their preparation, and their positive **photosensitive** resin compositions and **photosensitive** materials

ST pyrenesulfonic acid onium salt photoacid generator pos **photoresist**; photoacid generator i line sensitive

IT Positive photoresists

(i-line; preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT Onium compounds
Sulfonic acids, uses
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT 158593-28-3 603117-24-4 **603117-27-7** **603117-29-9**
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT 1483-72-3, Diphenyliodonium chloride 6358-69-6, Pyranine
RL: RCT (Reactant); RACT (Reactant or reagent)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

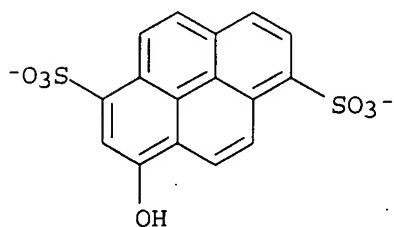
IT 129674-22-2, p-(tert-Butyloxycarbonyloxy)styrene-p-hydroxystyrene copolymer
RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

IT **603117-27-7** **603117-29-9**
RL: CAT (Catalyst use); USES (Uses)
(preparation of pyrenesulfonic acid onium salts for photoacid generator sensitive to 365-nm light for pos. **photoresist**)

RN 603117-27-7 CAPLUS
CN Sulfonium, triphenyl-, salt with 3-hydroxy-1,6-pyrenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

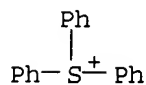
CM 1

CRN 603117-26-6
CMF C16 H8 O7 S2



CM 2

CRN 18393-55-0
CMF C18 H15 S

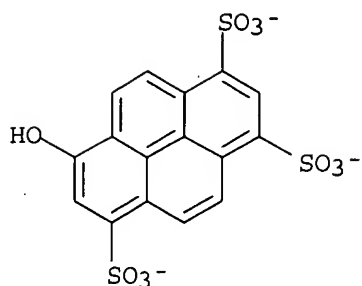


RN 603117-29-9 CAPLUS
CN Sulfonium, triphenyl-, salt with 8-hydroxy-1,3,6-pyrenetrisulfonic acid (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 57206-23-2

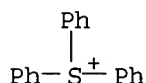
CMF C16 H7 O10 S3



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 10 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2002:707555 CAPLUS

DN 137:255361

TI **Heat**-mode negative-working lithographic printing master plate containing onium salt polymerization initiator

IN Shimada, Kazuto; Sorori, Tadahiro

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 34 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002268217	A2	20020918	JP 2001-69168	20010312
	US 2003017411	A1	20030123	US 2002-93746	20020311
	US 6623910	B2	20030923		
PRAI	JP 2001-69168	A	20010312		

TI **Heat**-mode negative-working lithographic printing master plate containing onium salt polymerization initiator

AB The **heat**-mode neg.-working lithog. printing master plate comprises an IR-laser recordable **photosensitive** layer on a support which contains (a) a light-to-**heat** conversion agent, (b) a compound having a polymerizable unsatd. group; and (c) an onium salt having a polyvalent counter ion. . . anion increased an electron d. of the counter anion, resulting in promoting a decomposition of the onium salt upon receiving **heat**.

ST onium salt polymn initiator lithog printing master plate; **heat** mode neg working lithog printing master plate; diazonium iodonium sulfonium salt polymn initiator

IT Lithographic plates
Polymerization catalysts

(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT Onium compounds

Sulfonium compounds

RL: CAT (Catalyst use); USES (Uses)

(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT Polyurethanes, uses

RL: TEM (Technical or engineered material use); USES (Uses)

(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT Onium compounds

RL: CAT (Catalyst use); USES (Uses)

(iodonium; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 57592-66-2, Pentaerythritol tetraacrylate homopolymer 139385-71-0, Glycerin dimethacrylate-hexamethylenediisocyanate copolymer

RL: TEM (Technical or engineered material use); USES (Uses)

(**heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 183745-01-9 460337-33-1 460337-34-2

RL: TEM (Technical or engineered material use); USES (Uses)

(light-to-**heat** conversion agent; **heat**-mode

neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT 460337-35-3 460337-36-4 460337-37-5 **460337-38-6**

460337-39-7 460337-41-1 460337-42-2 460337-43-3 460337-44-4

460337-46-6 460337-47-7 460337-48-8

RL: CAT (Catalyst use); USES (Uses)

(polymerization initiator; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

IT **460337-38-6**

RL: CAT (Catalyst use); USES (Uses)

(polymerization initiator; **heat**-mode neg.-working lithog. printing master plate containing onium salt polymerization initiator)

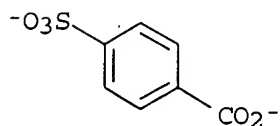
RN 460337-38-6 CAPLUS

CN Sulfonium, bis(4-chlorophenyl)phenyl-, salt with 4-sulfobenzoic acid (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 161664-30-8

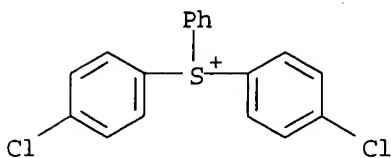
CMF C7 H4 O5 S



CM 2

CRN 127855-17-8

CMF C18 H13 Cl2 S



L19 ANSWER 11 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2001:261336 CAPLUS

DN 134:303007

TI Positive-working 220 nm light-sensitive chemically amplified
photoresist composition containing specific acid generator

IN Kodama, Kunihiro; Sato, Kenichiro; Aogo, Toshiaki

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 51 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001100402	A2	20010413	JP 1999-273160	19990927
	US 6410204	B1	20020625	US 2000-669907	20000927
PRAI	JP 1999-273160	A	19990927		

TI Positive-working 220 nm light-sensitive chemically amplified
photoresist composition containing specific acid generator

ST pos working light sensitive amplified **photoresist** compn
photoacid generator

IT Positive photoresists
Semiconductor device fabrication

(pos.-working 220 nm light-sensitive **photoresist** composition)
IT 71-43-2, Benzene, reactions 85-47-2, 1-Naphthalenesulfonic acid
945-51-7, Diphenyl sulfoxide 2049-95-8, tert-Amylbenzene 4270-70-6,
Triphenylsulfonium chloride 7758-05-6, Potassium iodate 12027-06-4,
Ammonium iodide

RL: RCT (Reactant); RACT (Reactant or reagent)

(photoacid generator in pos.-working chemical amplified
photoresist composition)

IT 3744-08-9P, Triphenylsulfonium iodide 249300-51-4DP,
Iodonium,bis[4-(1,1-dimethylpropyl)phenyl]-, salt with sulfate

RL: RCT (Reactant); SPN (Synthetic preparation); PREP (Preparation); RACT
(Reactant or reagent)

(photoacid generator in pos.-working chemical amplified
photoresist composition)

IT 13612-82-3P 14721-86-9P 137309-38-7P 137309-39-8P 220155-99-7P
334541-40-1P 334541-43-4P 334541-46-7P 334541-49-0P
334541-52-5P 334541-54-7P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(photoacid generator in pos.-working chemical amplified
photoresist composition)

IT 334541-40-1P 334541-46-7P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(photoacid generator in pos.-working chemical amplified
photoresist composition)

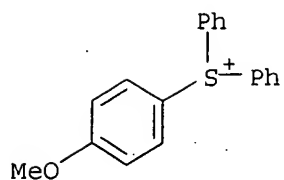
RN 334541-40-1 CAPLUS

CN Sulfonium, (4-methoxyphenyl)diphenyl-, salt with 6,7-dihydroxy-2-
naphthalenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 70084-23-0

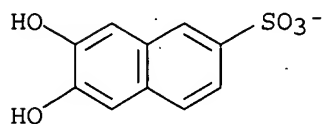
CMF C19 H17 O S



CM 2

CRN 32743-86-5

CMF C10 H7 O5 S



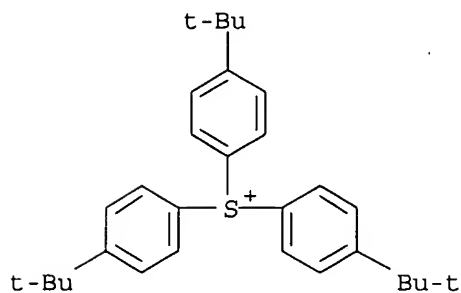
RN 334541-46-7 CAPLUS

CN Sulfonium, tris[4-(1,1-dimethylethyl)phenyl]-, salt with
6,7-dihydroxy-2-naphthalenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 91815-56-4

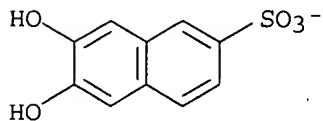
CMF C30 H39 S



CM 2

CRN 32743-86-5

CMF C10 H7 O5 S



L19 ANSWER 12 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1998:106203 CAPLUS

DN 128:198666

TI Negative-working presensitized lithographic plate useful for direct
platemaking

IN Kobayashi, Fumikazu

PA Fuji Photo Film Co., Ltd., Japan
 SO Jpn. Kokai Tokkyo Koho, 33 pp.
 CODEN: JKXXAF
 DT Patent
 LA Japanese
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10039509	A2	19980213	JP 1996-192517	19960722
	JP 3645362	B2	20050511		
	US 5965319	A	19991012	US 1997-891834	19970714
PRAI	JP 1996-192517	A	19960722		

AB . . . of platemaking directly from digital data using IR lasers and shows good storage stability, broader latitude in the condition of **heat** treatment after exposure, and high printing durability.

IT 87263-95-4P 137308-86-2P 137309-10-5P **137309-11-6P**
 161679-94-3P 166658-57-7P

RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)

(presensitized lithog. plate containing onium sulfonate, crosslinking agent, alkali-soluble resin, and IR absorbent)

IT **137309-11-6P**

RL: DEV (Device component use); PNU (Preparation, unclassified); PREP (Preparation); USES (Uses)

(presensitized lithog. plate containing onium sulfonate, crosslinking agent, alkali-soluble resin, and IR absorbent)

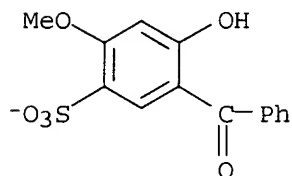
RN 137309-11-6 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM . 1

CRN 65994-36-7

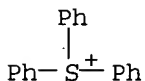
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 13 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1997:765308 CAPLUS

DN 128:108451

TI Sulfonium or iodonium disulfonates and positive-working **photosensitive** composition containing them

IN Aogo, Toshiaki; Sato, Kenichiro; Kodama, Kunihiro

PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 58 pp.
CODEN: JKXXAF

DT Patent
LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09309874	A2	19971202	JP 1996-125949	19960521

PRAI JP 1996-125949

OS MARPAT 128:108451

TI Sulfonium or iodonium disulfonates and positive-working
photosensitive composition containing them

AB . . . or II (R4-5 have the same definition as R1-3; Ar has the same
definition as above) are claimed. The pos.-working **photosensitive**
composition, useful for lithog. plate making, elec. circuit boards, etc.,
contains a resin having groups which are decomposed upon acids. . .

ST pos **photoresist** sulfonium iodonium photoacid generator;
disulfonate sulfonium iodonium photoacid generator **photoresist**;
resist photo sulfonium disulfonate photoacid generator

IT Positive photoresists
(preparation of sulfonium or iodonium disulfonates as photoacid generators
for pos.-working **photosensitive** composition)

IT 201156-46-9P 201156-50-5P 201156-52-7P
201156-54-9P 201156-55-0P 201156-57-2P 201156-58-3P
201156-60-7P 201156-61-8P 201302-74-1P 201302-77-4P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(preparation of sulfonium or iodonium disulfonates as photoacid generators
for pos.-working **photosensitive** composition)

IT 1483-72-3, Diphenyliodonium chloride 3709-43-1, 4,4'-Dinitrostilbene-
2,2'-disulfonic acid disodium salt 4270-70-6, Triphenylsulfonium
chloride 5421-53-4, 4,4'-Bis(tert-butylphenyl)iodonium chloride
27154-83-2 69031-60-3 201156-40-3 201156-41-4 201156-43-6

RL: RCT (Reactant); RACT (Reactant or reagent)

(preparation of sulfonium or iodonium disulfonates as photoacid generators
for pos.-working **photosensitive** composition)

IT 201156-63-0 201156-65-2 201156-66-3
201156-69-6 201156-71-0 201156-72-1 201302-80-9 201363-44-2

RL: TEM (Technical or engineered material use); USES (Uses)

(preparation of sulfonium or iodonium disulfonates as photoacid generators
for pos.-working **photosensitive** composition)

IT 201156-46-9P 201156-50-5P 201156-52-7P
201156-54-9P

RL: PNU (Preparation, unclassified); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(preparation of sulfonium or iodonium disulfonates as photoacid generators
for pos.-working **photosensitive** composition)

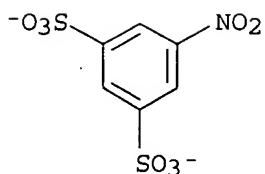
RN 201156-46-9 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-nitro-1,3-benzenedisulfonic acid (2:1)
(9CI) (CA INDEX NAME)

CM 1

CRN 201156-45-8

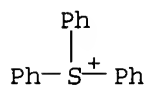
CMF C6 H3 N O8 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



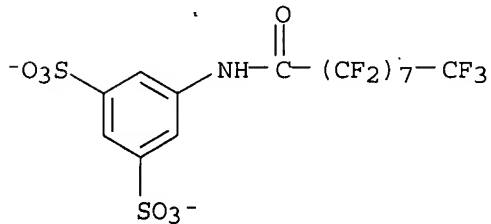
RN 201156-50-5 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-[(2,2,3,3,4,4,5,5,6,6,7,7,8,8,9,9,9-heptafluoro-1-oxononyl)amino]-1,3-benzenedisulfonic acid (2:1) (9CI)
(CA INDEX NAME)

CM 1

CRN 201156-49-2

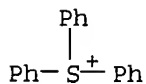
CMF C15 H4 F17 N O7 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



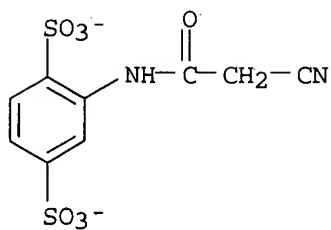
RN 201156-52-7 CAPLUS

CN Sulfonium, triphenyl-, salt with 2-[(cyanoacetyl)amino]-1,4-benzenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 201156-51-6

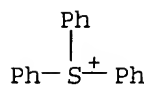
CMF C9 H6 N2 O7 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



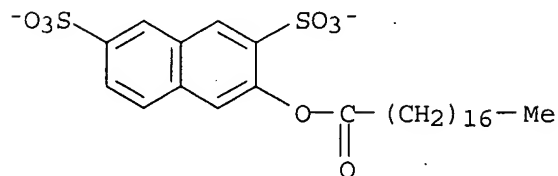
RN 201156-54-9 CAPLUS

CN Sulfonium, triphenyl-, salt with 3,6-disulfo-2-naphthalenyl octadecanoate (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 201156-53-8

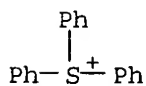
CMF C28 H40 O8 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



IT 201156-63-0 201156-65-2 201156-66-3

RL: TEM (Technical or engineered material use); USES (Uses)
(preparation of sulfonium or iodonium disulfonates as photoacid generators for pos.-working **photosensitive** composition)

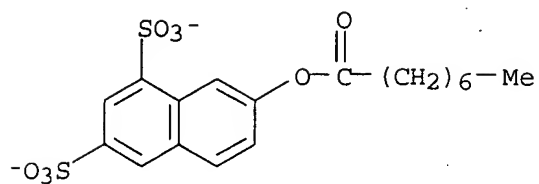
RN 201156-63-0 CAPLUS

CN Sulfonium, bis(4-hydroxyphenyl)phenyl-, salt with 6,8-disulfo-2-naphthalenyl octanoate (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 201156-62-9

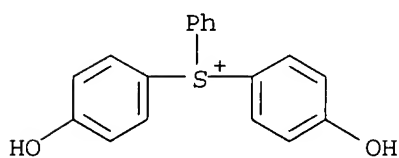
CMF C18 H20 O8 S2



CM 2

CRN 120397-56-0

CMF C18 H15 O2 S



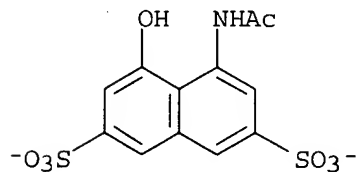
RN 201156-65-2 CAPLUS

CN Sulfonium, triphenyl-, salt with 4-(acetylamino)-5-hydroxy-2,7-naphthalenedisulfonic acid (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 201156-64-1

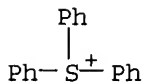
CMF C12 H9 N O8 S2



CM 2

CRN 18393-55-0

CMF C18 H15 S



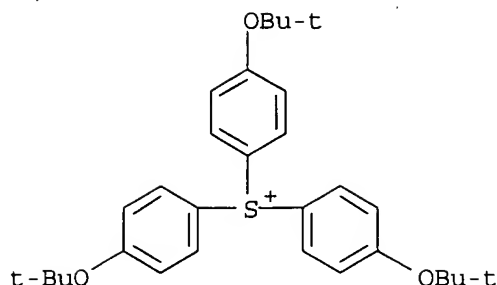
RN 201156-66-3 CAPLUS

CN Sulfonium, tris[4-(1,1-dimethylethoxy)phenyl]-, 2,6-naphthalenedisulfonate (2:1) (9CI) (CA INDEX NAME)

CM 1

CRN 137455-55-1

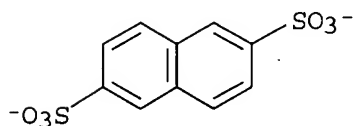
CMF C30 H39 O3 S



CM 2

CRN 55077-34-4

CMF C10 H6 O6 S2



L19 ANSWER 14 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1995:386319 CAPLUS

DN 122:136009

TI Washfast dyed polyester fabrics with improved color brightness and depth

IN Yamada, Setsuo; Kobayashi, Shigenobu

PA Teijin Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06330463	A2	19941129	JP 1993-121438	19930524
PRAI	JP 1993-121438		19930524		

AB The fabrics comprise polyester fibers dyed with dyes (e.g., cationic dyes) and have the surface coated with **heat**-curable vinyl polymers containing oxazoline groups in the side chain or derivs. thereof and have color yield value (ΔE ; JIS Z-8730-1980). . . spun, made into a woven fabric, dyed with a solution containing 2% (on fiber) C.I. Basic Blue 75, washed, dried, **heat** set, treated with an aqueous solution containing 10% Cl-4 alkyl acrylate-styrene-vinyloxazoline copolymer to 50% pickup, dried, and **heat** treated 1 min at 170° to give a colored fabric with ΔE 12.4 initially and 12.6 after 5 washings.

IT 161261-41-2

RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(fiber; washfast dyed polyester fabrics with improved color brightness and depth)

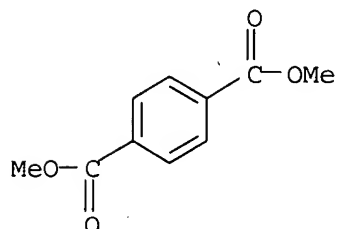
IT 161261-41-2

RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(fiber; washfast dyed polyester fabrics with improved color brightness and depth)

RN 161261-41-2 CAPLUS
 CN Sulfonium, tributyl-, salt with 5-sulfo-1,3-benzenedicarboxylic acid
 (1:1), polymer with dimethyl 1,4-benzenedicarboxylate and 1,2-ethanediol
 (9CI) (CA INDEX NAME)

CM 1

CRN 120-61-6
 CMF C10 H10 O4



CM 2

CRN 107-21-1
 CMF C2 H6 O2

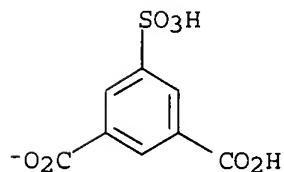
HO-CH₂-CH₂-OH

CM 3

CRN 161261-40-1
 CMF C12 H27 S . C8 H5 O7 S

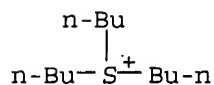
CM 4

CRN 65086-74-0
 CMF C8 H5 O7 S



CM 5

CRN 39895-78-8
 CMF C12 H27 S



L19 ANSWER 15 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1994:120755 CAPLUS

DN 120:120755

TI **Photosensitive** composition for lithographic plates and **photoresist**

IN Uenishi, Kazuya; Umehara, Akira; Aotani, Norimasa; Yamaoka, Tsugio

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05005993	A2	19930114	JP 1991-159093	19910628

PRAI JP 1991-159093 19910628

TI **Photosensitive** composition for lithographic plates and **photoresist**

ST **photosensitive** compn **photoresist** lithog plate; onium
arom sulfonate **photosensitive** compn

IT Lithographic plates

(manufacture of, **photosensitive** compns. for)

IT Phenolic resins, uses

RL: TEM (Technical or engineered material use); USES (Uses)
(novolak, **photoresist** compns. containing)

IT 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 74508-34-2
87261-04-9 137308-83-9 137308-84-0 137309-03-6 137309-10-5
137337-64-5 151461-54-0

RL: USES (Uses)

(**photosensitive** composition containing)

IT 137308-86-2P, Diphenyliodonium 9,10-dimethoxyanthracene-2-sulfonate
137309-11-6P

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, **photosensitive** composition containing)

IT **137309-11-6P**

RL: SPN (Synthetic preparation); PREP (Preparation)
(preparation and use of, **photosensitive** composition containing)

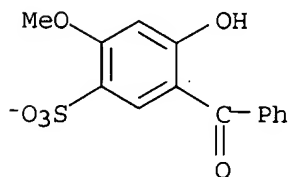
RN 137309-11-6 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7

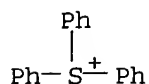
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 16 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1993:505909 CAPLUS

DN 119:105909

TI **Photosensitive** compositions with high photosensitivity and resolution

IN Uenishi, Kazuya; Aotani, Norimasa; Umehara, Akira; Yamaoka, Tsugio

PA Fuji Photo Film Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 18 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

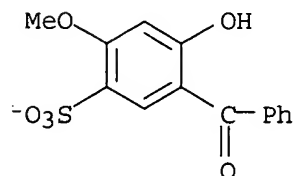
FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05045878	A2	19930226	JP 1991-204205	19910814
PRAI	JP 1991-204205		19910814		
OS	MARPAT 119:105909				
TI	Photosensitive compositions with high photosensitivity and resolution				
ST	photosensitive compn onium arom sulfonate				
IT	2203-14-7 3089-11-0, Hexamethoxymethylmelamine 24979-70-2, Poly(p-hydroxystyrene) 27029-76-1, m-Cresol-p-cresol-formaldehyde copolymer 137308-83-9 137308-92-0 137309-13-8 RL: USES (Uses) (photoresist containing)				
IT	137308-86-2P 137309-11-6P RL: PREP (Preparation) (preparation of, photoresist containing)				
IT	137309-11-6P RL: PREP (Preparation) (preparation of, photoresist containing)				
RN	137309-11-6 CAPLUS				
CN	Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)				

CM 1

CRN 65994-36-7

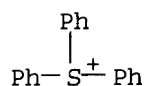
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



L19 ANSWER 17 OF 17 CAPLUS COPYRIGHT 2005 ACS on STN

AN 1991:644043 CAPLUS

DN 115:244043

TI Positive-working **photosensitive** composition

IN Aotani, Yoshimasa; Umehara, Akira; Yamaoka, Tsuguo

PA Fuji Photo Film Co., Ltd., Japan

SO Ger. Offen., 22 pp.

CODEN: GWXXBX

DT Patent

LA German

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4035425	A1	19910516	DE 1990-4035425	19901107
	DE 4035425	C2	19990527		
	JP 03154059	A2	19910702	JP 1989-294422	19891113
	US 5202216	A	19930413	US 1990-608801	19901105
PRAI	JP 1989-294422	A	19891113		

TI Positive-working **photosensitive** composition

ST **photosensitive** compn sensitivity contrast; onium salt sulfonic acid

IT Onium compounds

RL: USES (Uses)

(of sulfonic acids, **photosensitive** compns. containing)

IT Lithographic plates

(**photosensitive**, pos.-working, polymers and onium compound sulfonic acid salts in)

IT	137308-83-9P	137308-84-0P	137308-86-2P	137308-87-3P	137308-88-4P
	137308-89-5P	137308-90-8P	137308-92-0P	137308-94-2P	137308-96-4P
	137308-98-6P	137309-00-3P	137309-01-4P	137309-03-6P	137309-04-7P
	137309-05-8P	137309-06-9P	137309-07-0P	137309-08-1P	137309-09-2P
	137309-10-5P	137309-11-6P	137309-12-7P	137309-13-8P	
	137309-14-9P	137309-15-0P	137309-16-1P	137309-17-2P	137309-18-3P
	137309-20-7P	137309-22-9P	137309-23-0P	137309-25-2P	137309-26-3P
	137309-27-4P	137309-28-5P	137309-29-6P	137309-30-9P	137309-33-2P
	137309-34-3P	137309-35-4P	137309-36-5P	137309-37-6P	137309-38-7P
	137309-39-8P	137309-40-1P	137337-63-4P	137337-64-5P	137337-66-7P

RL: SPN (Synthetic preparation); PREP (Preparation)

(preparation and use of, in **photosensitive** composition)

IT **137309-11-6P**

RL: SPN (Synthetic preparation); PREP (Preparation)

(preparation and use of, in **photosensitive** composition)

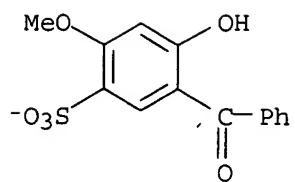
RN 137309-11-6 CAPLUS

CN Sulfonium, triphenyl-, salt with 5-benzoyl-4-hydroxy-2-methoxybenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 65994-36-7

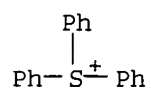
CMF C14 H11 O6 S



CM 2

CRN 18393-55-0

CMF C18 H15 S



=>

(FILE 'HOME' ENTERED AT 12:27:06 ON 25 JUL 2005)

FILE 'REGISTRY' ENTERED AT 12:27:17 ON 25 JUL 2005

L1 STRUCTURE UPLOADED
L2 STRUCTURE UPLOADED
L3 STRUCTURE UPLOADED
L4 81 S L1 FULL
L5 51766 S L2 FULL
L6 83641 S L3 FULL
L7 40 S (L4 OR L5 OR L6) AND (SULFONIUM OR TRIPHENYLSULFONIUM)

FILE 'CAPLUS' ENTERED AT 12:30:00 ON 25 JUL 2005

L8 26 S L7
L9 174 S PHENOL NOVOLAC
L10 2728 S PHENOL NOVOLAK
L11 7748 S PHENOLIC NOVOLAK
L12 147 S PHENOLIC NOVOLAC
L13 0 S L8 AND (L9 OR L10 OR L11 OR L12)
L14 381 S PHOTO THERMAL
L15 0 S L8 AND L14
L16 11801 S PRINTING PLATE
L17 2 S L8 AND L16
L18 2240033 S PHOTORESIST OR IMAGE OR PHOTSENSITIVE OR THERMAL OR HEAT
L19 17 S L8 AND L18

=> d. l17 1-2

L17 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:633141 CAPLUS

DN 141:181996

TI Image forming material

IN Iwato, Kaoru

PA Fuji Photo Film Co., Ltd., Japan

SO U.S. Pat. Appl. Publ., 67 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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PI	US 2004152012	A1	20040805	US 2004-760497	20040121
	JP 2004226794	A2	20040812	JP 2003-15905	20030124
	JP 2004233854	A2	20040819	JP 2003-24499	20030131
PRAI	JP 2003-15905	A	20030124		
	JP 2003-24499	A	20030131		
OS	MARPAT 141:181996				

L17 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:246983 CAPLUS

DN 140:294802

TI Image forming material

IN Iwato, Kaoru; Sorori, Tadahiro

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 94 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	----	-----	-----
PI	EP 1400350	A2	20040324	EP 2003-20551	20030917
	EP 1400350	A3	20040414		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK

JP 2004109320	A2	20040408	JP 2002-269900	20020917
JP 2004126049	A2	20040422	JP 2002-287818	20020930
US 2004067435	A1	20040408	US 2003-662534	20030916
PRAI JP 2002-269900	A	20020917		
JP 2002-287818	A	20020930		
OS MARPAT 140:294802				

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